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(WO/2000/058533) REACTION CHAMBER FOR AN EPITAXIAL REACTOR[Biblio. Data](#)[Description](#)[Claims](#)[National Phase](#)[Notices](#)[Documents](#)

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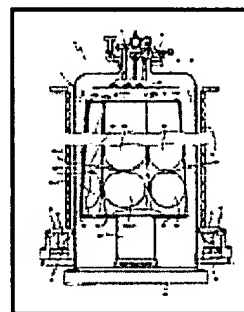
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Agent: MICHELOTTI, Guiliano; Galleria San Babila, 4/C I-20122 Milano (IT).**Priority Data:** MI99A000607 25.03.1999 IT**Title:** REACTION CHAMBER FOR AN EPITAXIAL REACTOR

Abstract: Reaction chamber (10) for an epitaxial reactor comprising a belljar (14) made of insulating, transparent and chemically resistant material, a susceptor (24) provided with disk-shaped cavities (34a-n) for receiving wafers (36a-n) of material to be treated and having an insulating and chemically resistant plate (40) arranged above it, and a diffuser (54) consisting of a plurality of outlet pipes (106a-f) mounted on a cap (52) fixed to an upper opening (50) of the belljar (14).

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